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APPLICATION NO.	F	ILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/706,266		11/13/2003	Takaaki Shiota	061063-0306825	5650	
909	7590	09/29/2005		EXAM	INER	
		THROP SHAW PI	KUNEMUND	KUNEMUND, ROBERT M		
P.O. BOX 1 MCLEAN,		02		ART UNIT PAPER NUMBER		
ŕ				1722		

DATE MAILED: 09/29/2005

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)					
	10/706,266	SHIOTA ET AL.					
Office Action Summary	Examiner	Art Unit					
	Robert M. Kunemund	1722					
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply							
A SHORTENED STATUTORY PERIOD FOR REP WHICHEVER IS LONGER, FROM THE MAILING I - Extensions of time may be available under the provisions of 37 CFR 1 after SIX (6) MONTHS from the mailing date of this communication. If NO period for reply is specified above, the maximum statutory perior - Failure to reply within the set or extended period for reply will, by statu Any reply received by the Office later than three months after the mail earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNICATION .136(a). In no event, however, may a reply be will apply and will expire SIX (6) MONTHS from the cause the application to become ABANDON	ON. timely filed om the mailing date of this communication. NED (35 U.S.C. § 133).					
Status							
1)⊠ Responsive to communication(s) filed on 20.	July 2005						
_	is action is non-final.	•					
, <u> </u>		procedution as to the morits is					
	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
closed in accordance with the practice under	Ex parte Quayle, 1955 C.D. 11,	455 O.G. 215.					
Disposition of Claims							
4)⊠ Claim(s) <u>1-3 and 6-28</u> is/are pending in the application.							
4a) Of the above claim(s) is/are withdrawn from consideration.							
5) Claim(s) is/are allowed.							
6)⊠ Claim(s) <u>1-3 and 6-28</u> is/are rejected.							
7) Claim(s) is/are objected to.							
8) Claim(s) are subject to restriction and							
Application Papers							
9) The specification is objected to by the Examiner.							
10) The drawing(s) filed on is/are: a) accepted or b) objected to by the Examiner.							
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).							
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d). 11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.							
	Examiner. Note the attached Offic	e Action of form P1O-152.					
Priority under 35 U.S.C. § 119							
12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).							
a) ☐ All b) ☐ Some * c) ☐ None of:							
1. Certified copies of the priority documents have been received.							
2. Certified copies of the priority documents have been received in Application No							
3. Copies of the certified copies of the priority documents have been received in this National Stage							
application from the International Bureau (PCT Rule 17.2(a)).							
* See the attached detailed Office action for a list of the certified copies not received.							
Attachmont/a)							
Attachment(s) 1) Notice of References Cited (PTO-892)	4) 🔲 Interview Summa	ev (RTO 412)					
2) Notice of Draftsperson's Patent Drawing Review (PTO-948)	4) Interview Summa Paper No(s)/Mail						
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08	3) 5) Notice of Informal	Patent Application (PTO-152)					
Paper No(s)/Mail Date	6)						
U.S. Patent and Trademark Office PTOL-326 (Rev. 7-05) Office	Action Summary	Part of Paper No./Mail Date 20050926					

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DETAILED ACTION

Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

Claims 1 to 3, 6, 9 to 20 and 25 to 28 are rejected under 35 U.S.C. 103(a) as being unpatentable over Falster (6,849,901).

The Falster reference teaches a method of creating a silicon wafer with an epitiaxial defect free layer on it, note, entire reference. A silicon wafer is creating by the seed pulling method where the V/G ratio is controlled and keeps at a level to create the desired silicon crystal. The V/G is taught to be a result effective variable, note col. 27. The wafer is sliced from the grown crystal. The wafer is then subjected to a heat treatment at temperatures above 1,100°c in an inert atmosphere. The annealing or

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treatment conditions also affect the crystal, note cols, 18 and 19. The sole difference between the instant claims and the prior art is the defects in the wafer. However, in the absence of unexpected results, it would have been obvious to one of ordinary skill in the art to determine through routine experimentation the optimum, operable properties of the wafer, defects in the Falster process in order to create the desired wafer as the reference clearly shows changing conditions effect the defects in the wafers.

Claims 7, 8 and 21 to 24 are rejected under 35 U.S.C. 103(a) as being unpatentable over Falster (6,849,901).

The Falster reference is relied on for the same reasons as stated, supra, and differs in the removal of the silicon dioxide. However, in the absence of unexpected results, it would have been obvious to one of ordinary skill in the art to determine through routine experimentation the optimum, operable removal time of the silicon dioxide in the Falster process in order to treat the wafer without having oxygen present.

Response to Applicants' Response

Applicant's arguments filed July 20, 2005 have been fully considered but they are not persuasive.

Applicants' argument concerning the Falster et al reference is noted. However, the reference does teach that the processing conditions can be modified by one of ordinary skill in the art to modify the wafer properties, including defects. The process changes are the same parameters that applicants use. Therefore, one of ordinary skill

in the art would have known to modify the process and hence the wafer of the Falster et al reference to obtain the instantly claimed wafer.

Applicants' argument concerning the annealing in the Falster et al reference has been considered and not deemed persuasive. However, the Falster et al also teaches that the annealing conditions as not so limited to the scope that has been argued by applicants. In fact, the annealing can be done over a broader range of conditions.

THIS ACTION IS MADE FINAL. Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the mailing date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Robert M. Kunemund whose telephone number is 571-272-1464. The examiner can normally be reached on 8 hours.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Duane Smith can be reached on 571-272-1166. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

RMK

PRIMARY EXAMINER